

Electrothermal HBT modeling

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Outline

- Introduction
- 3D numerical heat flow equation solver (THERMO)
- Green's function approach
- Test structure for determining thermal coupling
- Summary

Introduction

- Shrinking device dimensions
 - higher electric fields and increased *self-heating*
 - increasing impact on *carrier transport* and *reliability* of the device
- Increased packing density
 - higher thermal *interaction* between neighboring devices (thermal coupling)
 - detect/avoid *hot-spots* in larger devices (e.g. PA-arrays)

=> in-house development

- accurate numerical (discretized) solution (THERMO)
 - highest degree of flexibility (e.g. new material models, boundary conditions, structure, etc.)
 - access on internal quantities and verification of R_{th}/C_{th} extraction methods
 - thermal modeling beyond current materials and models (roadmapping)
- fast solution (Green's function)
 - support of compact model generation and device design, sizing, and optimization
 - fast investigation of temperature distribution across large structures
 - advanced thermal network development (static and transient beyond single R_{th} - C_{th} network)

3D numerical heat flow equation solver (THERMO)

- Numerical solution of the heat flow equation (1D to 3D):

$$\text{div}(\kappa(\vec{r}, T_L) \text{grad}(T_L)) = \alpha(\vec{r}, T_L) \frac{\partial T_L}{\partial t} - p_{\text{Diss}}(\vec{r})$$

- Features:
 - stationary and transient solutions
 - variety of physical models (thermal conductivity κ , thermal diffusivity α)
 - materials covered: Si, SiO₂, SiGe (preliminary model), etc. (parameters from literature)
 - post-processor for determining the most important parameters/quantities ($R_{\text{th}}, \dots$)
 - internal results saved as MAT-Files => can be directly accessed by Matlab/Octave
=> suitable for most applications

discretization and simulation time strongly depend on investigated structure

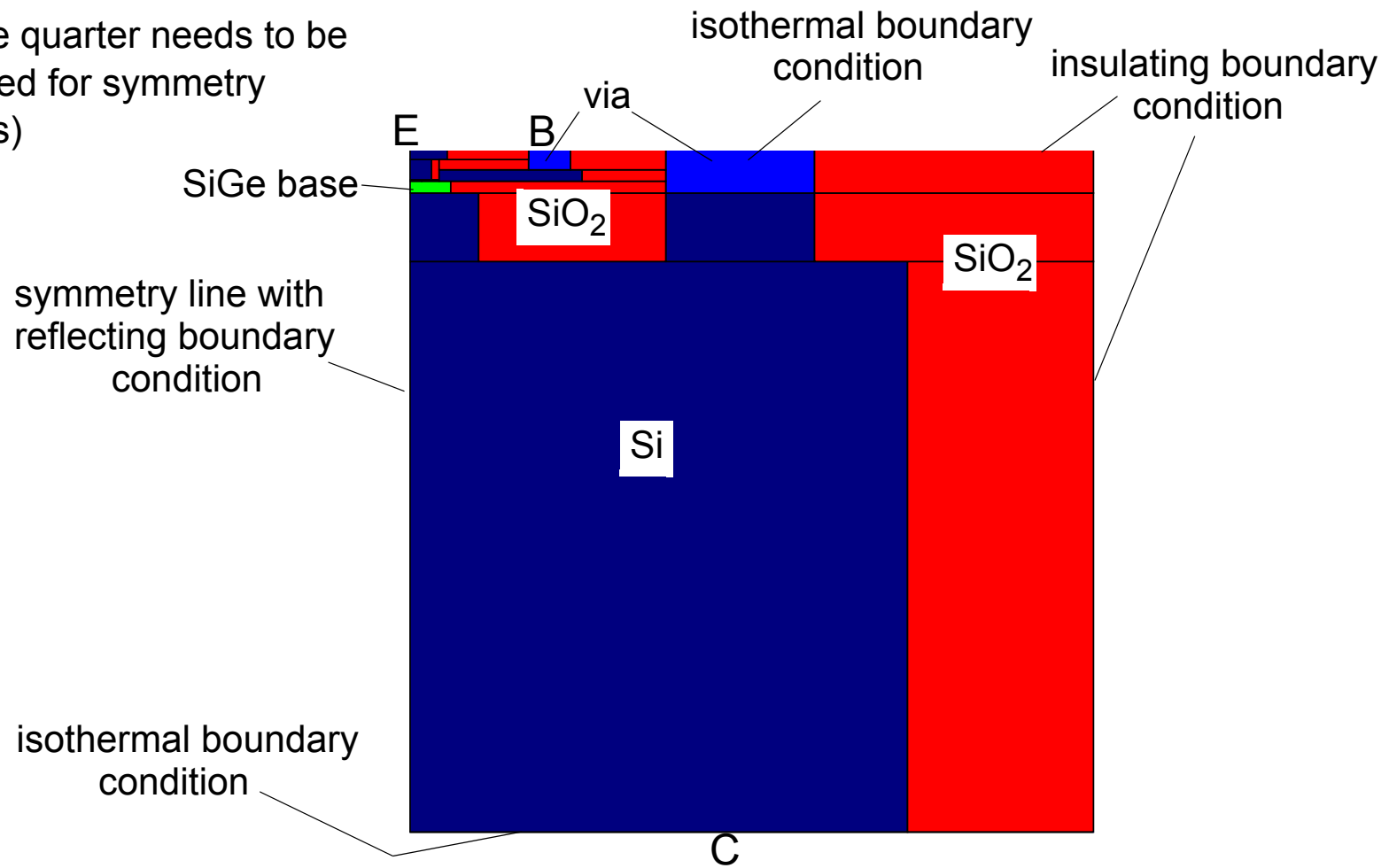
- Restrictions:
 - only rectangular domains (regular grids) so far => extension to non-regular if demanded
=> tool supports compact modeling and experimental data evaluation

Application example

3D simulation of a fabricated SiGe HBT (CBEBC)

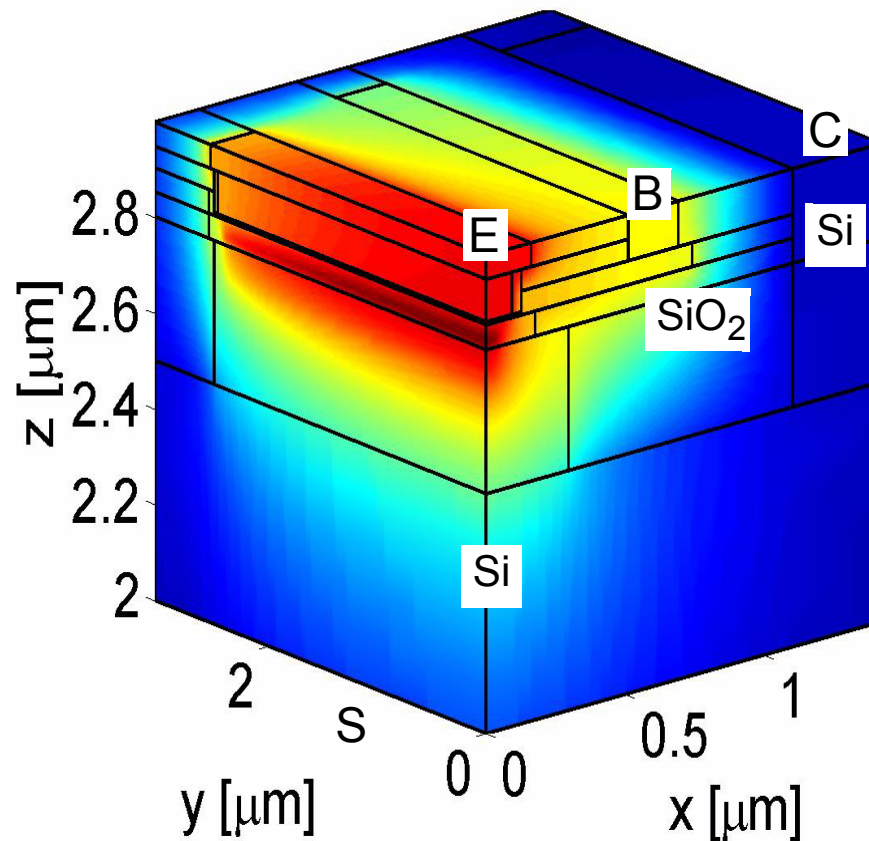
2D cross section of a 3D structure

(only one quarter needs to be simulated for symmetry reasons)



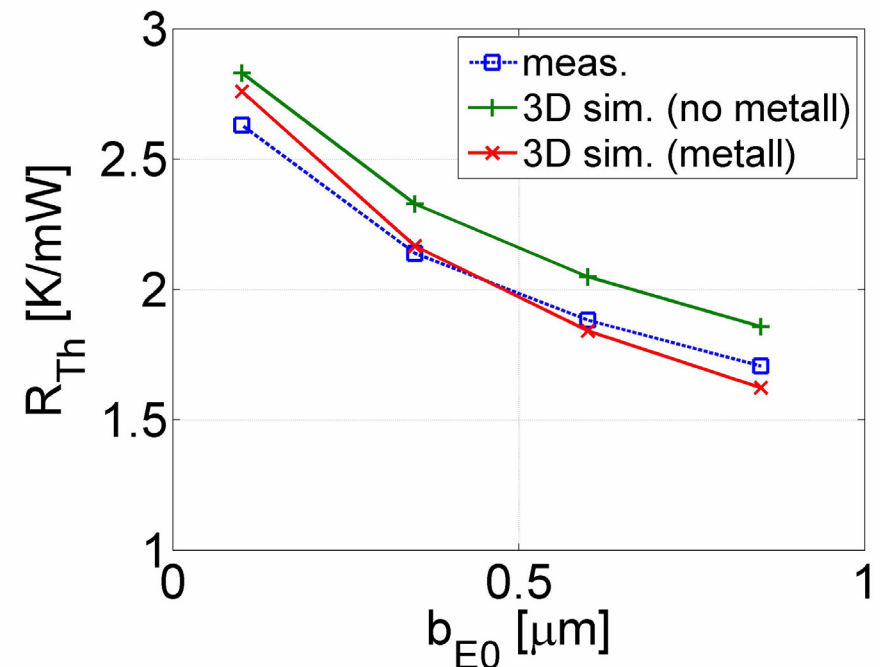
Results

3D temperature distribution



thermal resistance

simulated vs. measured
geometry dependence



=> impact of including surface metallization still approximate

=> Simulation and measured results agree with each other within range of uncertainty margin (structure, physical models and parameters)!

Green's function approach

... for 3D heat equation

- Semi-analytical solution of linear heat flow equation (1D to 3D):

$$\text{div}(\kappa \text{grad}(T_L)) = \alpha \frac{\partial T_L}{\partial t} - p_{\text{Diss}}(\vec{r})$$

- Features

- *stationary* and *transient* solutions for *small* AND *large* homogeneous domains, either (semi-) infinite (e.g. lateral substrate extension) or with laterally bounding regions (e.g. trench)
- possible boundary conditions:

- at surfaces: spatially variable temperature $T_L = f(\vec{r})$ or heat flux $\kappa \frac{\partial T_L}{\partial n} = f(\vec{r})$

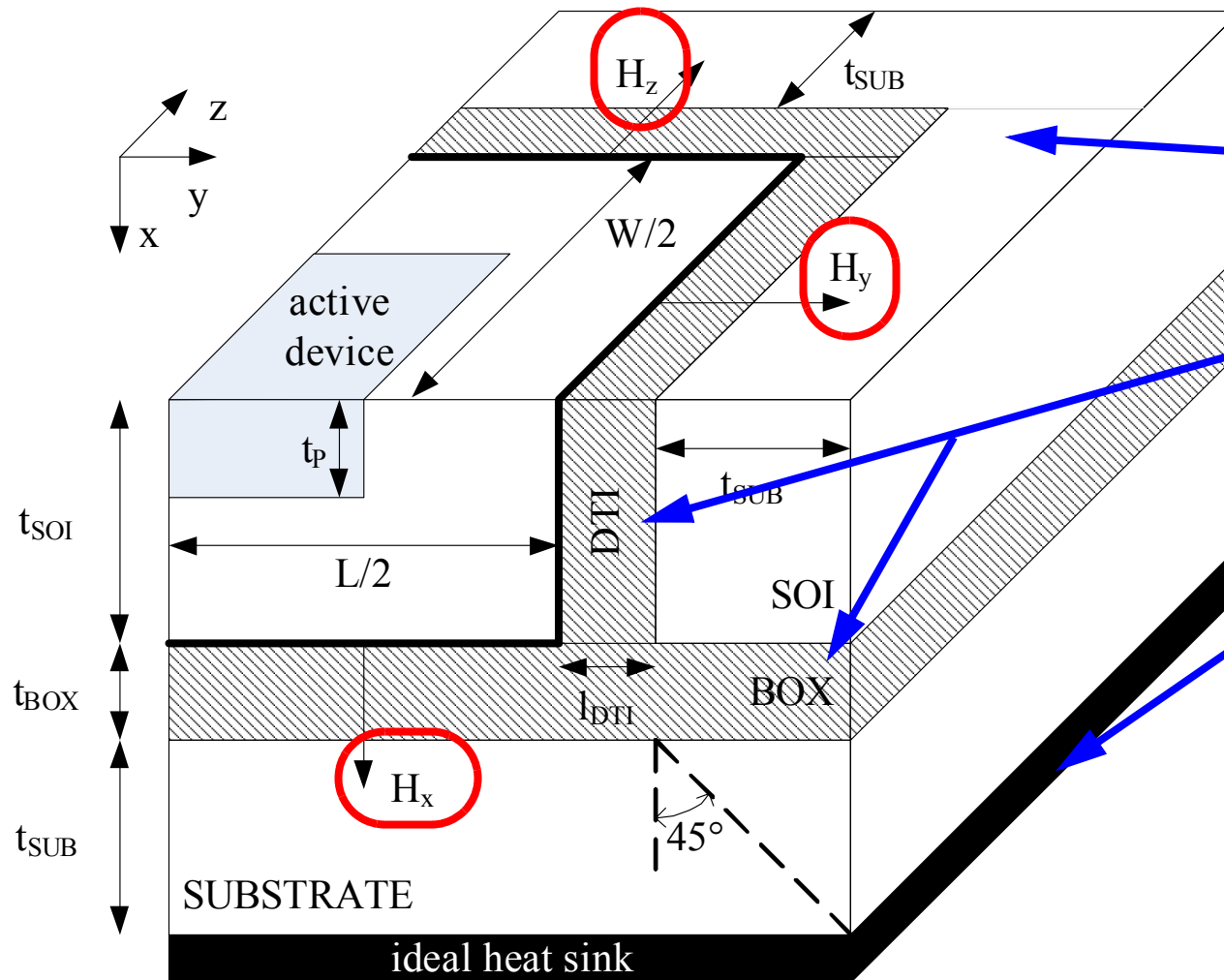
- at interfaces convection boundary condition $\kappa \frac{\partial T_L}{\partial n} + h T_L = 0$

with heat transfer coefficient h for, e.g., reduced heat flow into trench-walls or buried oxide with different thermal conductivity

- *temperature dependent non-linear thermal conductivity* can be included through *Kirchhoff transformation* ($\Rightarrow$ e.g. $R_{\text{th}}(T_L)$)

Example

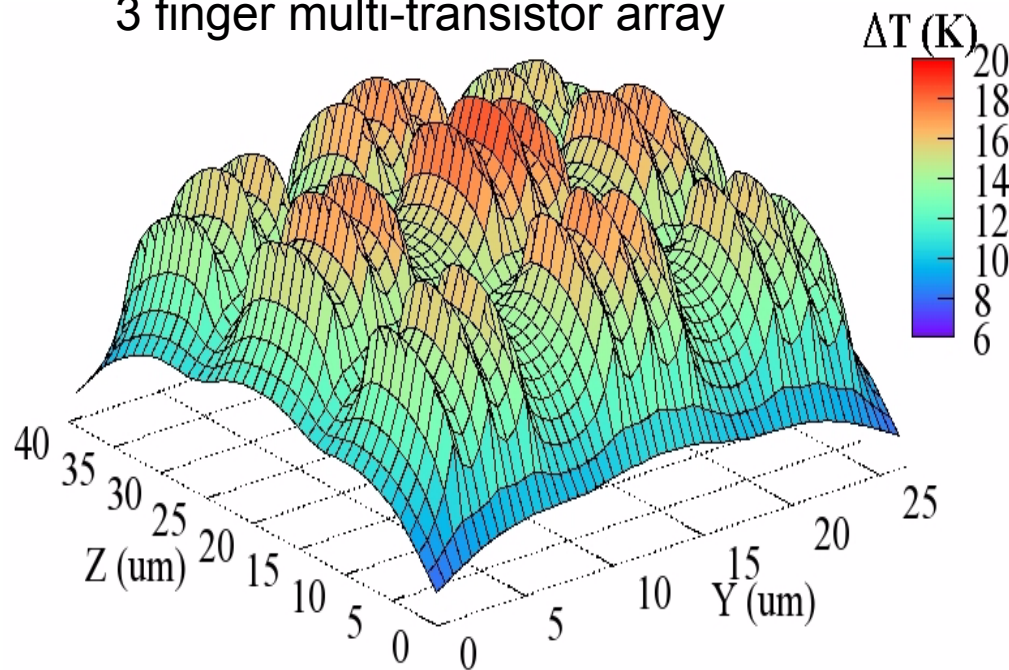
Thermal characterization of active devices fabricated in a SOI technology



- insulating boundary at substrate surface
- reduced heat flux into DTI and BOX modeled by convection b.c. (use of heat transfer coefficients H_x , H_y , H_z)
- isothermal b.c. at chip backside (heat sink)
- exploiting symmetry through use of insulating b.c.

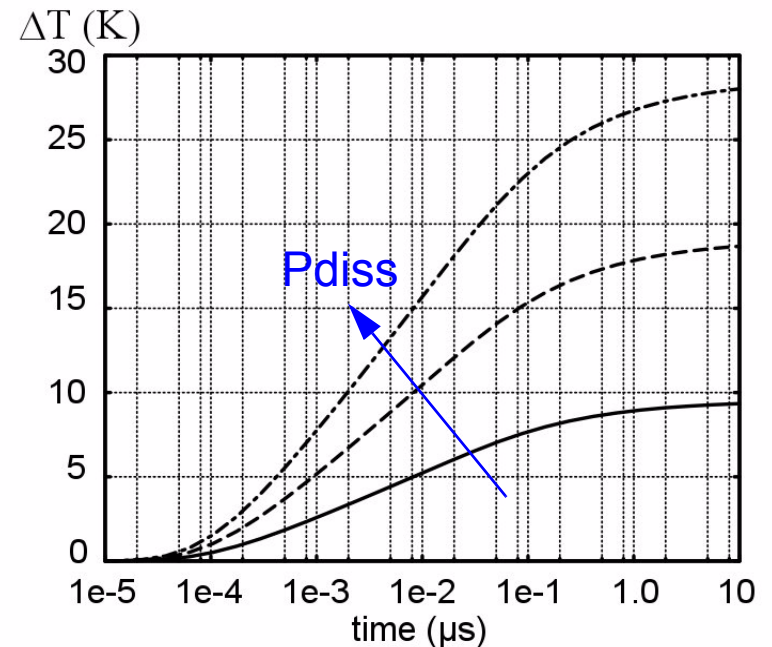
Applications

3D temperature distribution in a
3 finger multi-transistor array



=> detect peak temperature & reliability issues

time dependence of temperature
increase during dynamic operation



=> dynamic thermal network

- **fast** investigation/generation (seconds) of temperature distributions also **over large structures** (e.g. transistor arrays)
- **easily tunable** through use of results from measurements/extraction and numerical simulations

Application to circuit design and simulation

- supports efficient generation of thermal models (self-heating, thermal coupling)
- thermal models available in SPICE and VERILOG-A format

```
.SUBCKT THNET_L4 TN001 TN002 TN003 TNAMBIENT
```

```
simulator lang=spectre
```

```
simulator lang=spice
```

```
RTH001      Tn001      Tn001001      412.98
```

```
ETH001002   Tn001001   Tn001002   Tn002   Tn002001   0.3676
```

```
ETH001003   Tn001002   TNAMBIENT   Tn003   Tn003001   0.2585
```

```
RTH002      Tn002      Tn002001      412.98
```

```
ETH002001   Tn002001   Tn002002   Tn001   Tn001001   0.3676
```

```
.....
```

thermal network



```
analog
```

```
begin
```

```
Tnom = tnom+`P_CELSIUS0;
```

```
//=== self-heating source 1
```

```
rth001      = 412.98;
```

```
rth001_t = rth001 * exp(zetarth * ln(($temperature + V(Tn001)) / Tnom)
```

```
V(Tn001,Tn001001) <+ I(Tn001,Tn001001) * rth001_t;
```

```
//--- coupling source 1
```

```
c001002     = 0.367593;
```

```
c001003     = 0.258534;
```

```
V(Tn001001,Tn001002) <+ V(Tn002,Tn002001) * c001002;
```

```
V(Tn001002,THGND) <+ V(Tn003,Tn003001) * c001003;
```

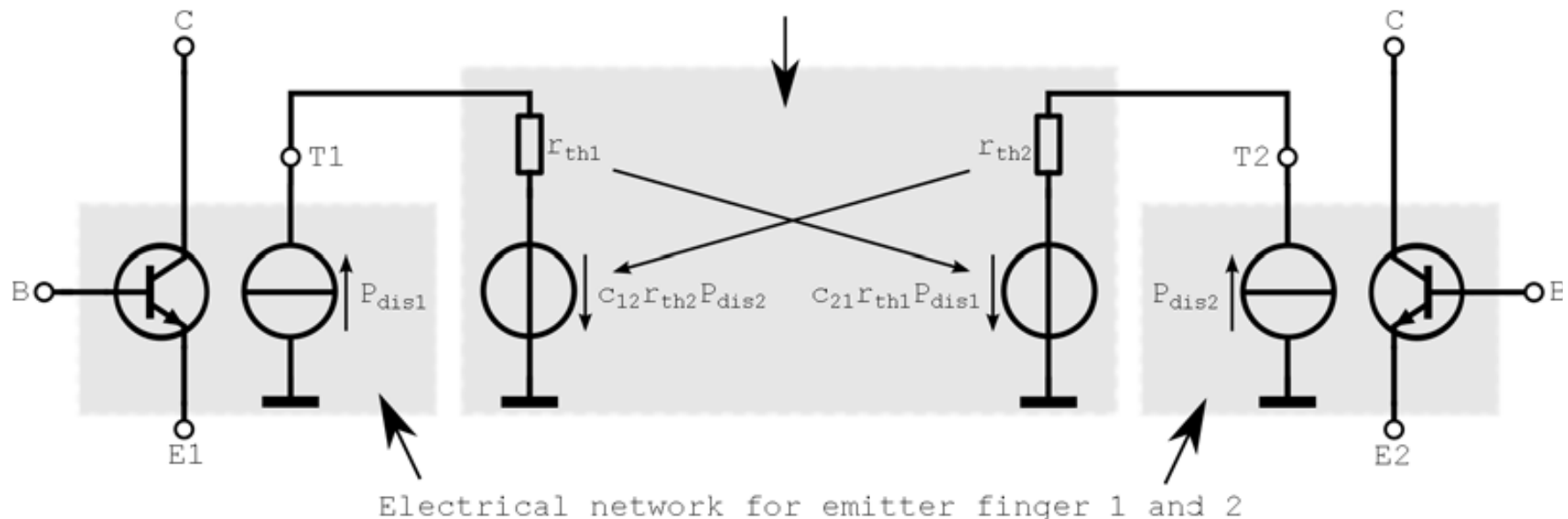
models



=> well-suited for device sizing and layout optimization w.r.t. thermal constraints

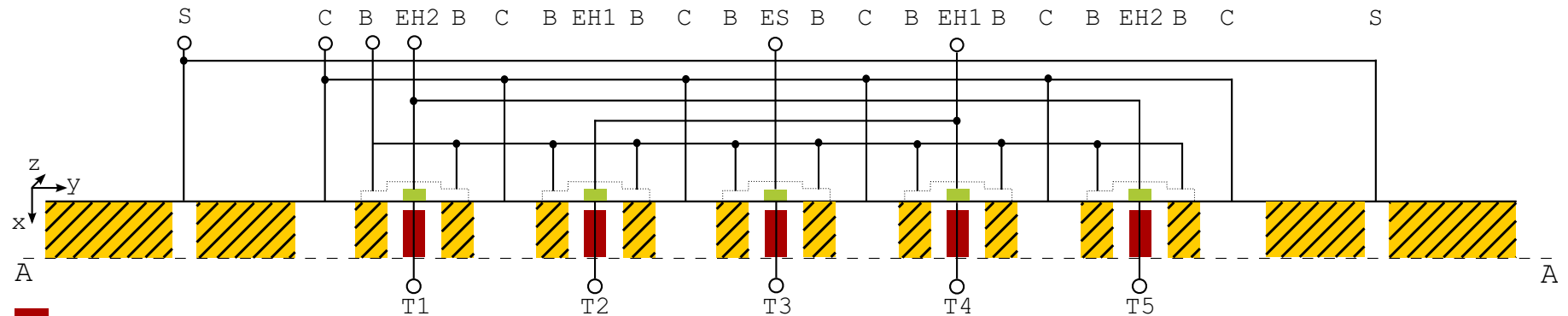
Modeling of static thermal coupling

thermal subcircuit for two-finger transistor or two transistor cells (example)



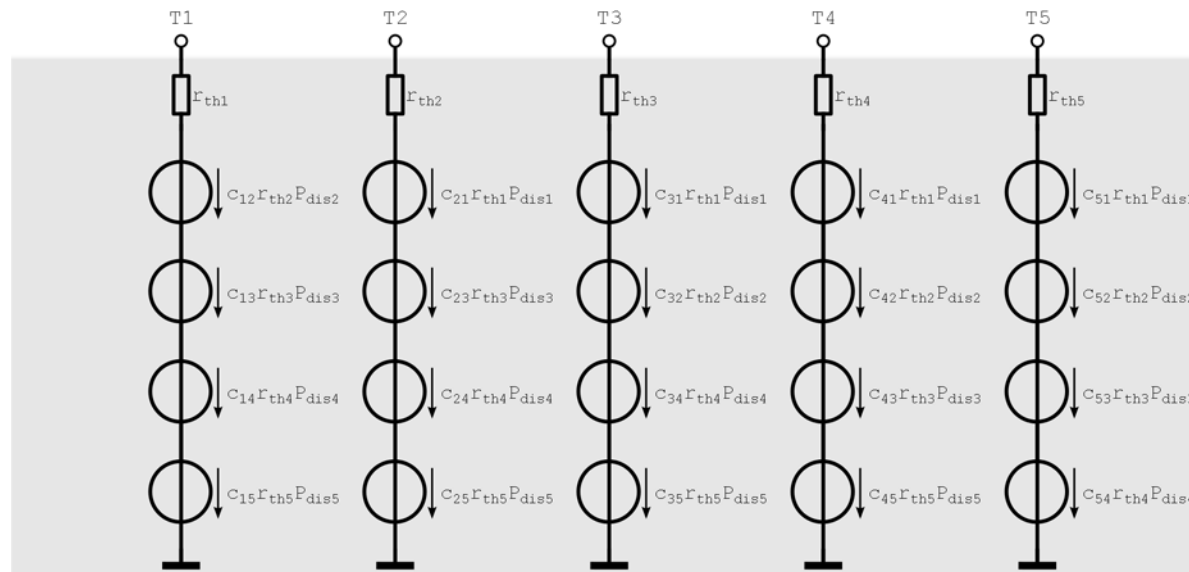
- need external access to thermal node in compact model
- set thermal resistance of compact model to infinity
- temperature dependence of thermal resistance in thermal subcircuit included through Verilog-A code

Test structure for determining thermal coupling



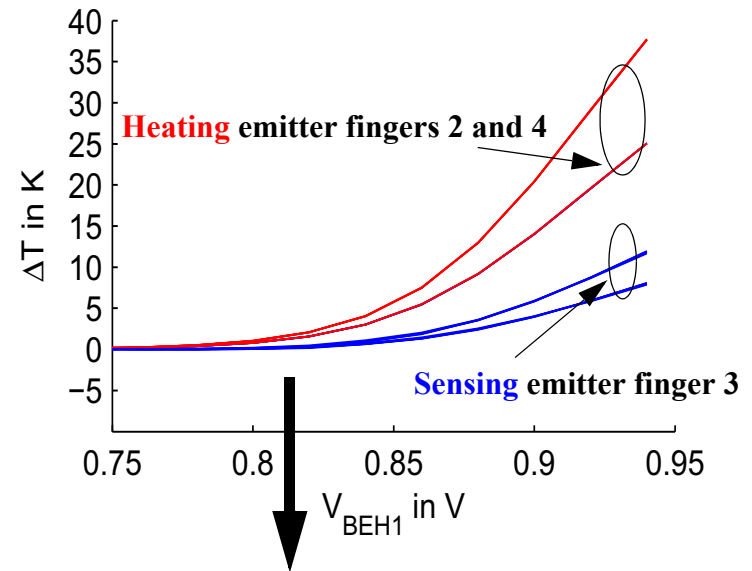
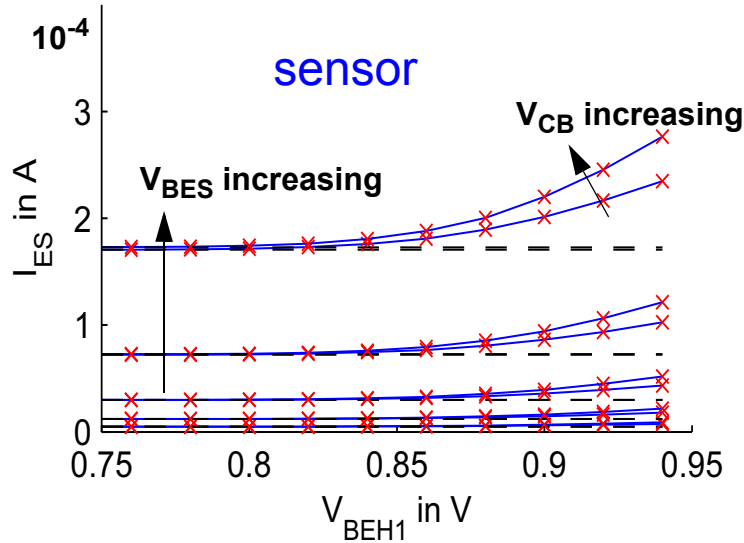
- Heat source domain
- Shallow trench
- Emitter

common S, B, C => use E as sensor and for adjusting power



=> fabricated in Si and investigated with THERMO, GF

Extraction of static thermal coupling

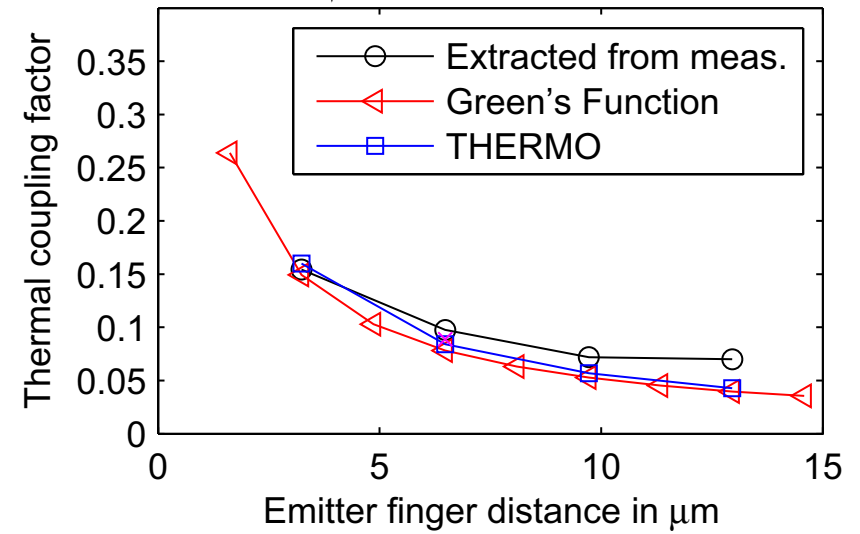


- extraction of (temperature) coupling from heating emitter fingers 2 and 4 to emitter finger 3

$$I_{ES} = I_{ESS}(T_{amb} + \Delta T) \exp\left(\frac{qV_{BES}}{mk_B(T + \Delta T)}\right)$$

$$\Delta T = r_{th,EH1} P_{EH1}$$

- Note: finger symmetry to be considered!



Summary

- Numerical thermal solver
 - captures complicated structures without simplifications
 - good agreement with measured R_{th} of state-of-the art devices
 - aid in tuning of GF-based method (e.g. determination of heat transfer coefficients)
 - highly valuable for (HBT) roadmapping
- GF-method
 - can be adjusted to model realistic structures (including DTI, SOI)
 - well-suited for large *and* small structures (i.e. including arrays of transistors)
 - fast but still accurate results for model generation and circuit design related applications (sizing, optimization)
- Accuracy depends on material models and parameters!!!
=> test structures and measurements needed for development/verification of material models for advanced devices

Acknowledgments

- IHP, Frankfurt/Oder, Germany
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